

MAGPULS MP 2 - AS Asymmetric BIPOLAR Pulse Power Supply





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World Wide Sales & Support through Dynamic Partners

www.magpuls.de

Highest flexibilty

Supreme performance for Ambitious Reactive Sputtering – Production of Flat Panel Displays, Solar Cells, Decorative / Hard Coatings.

MAGPULS Bi-Polar Pulse Power Supply series MP2 are designed for operating with dual magnetrons for reactive sputtering on substrates like glass, plastic & metal & semiconductors. Individual operating modes and enhanced ARC-management allows MP2 Pulse Power Supplies to operate very effectively in achieving high quality coatings. Typical applications are production of Flat Panel Displays, Solar Cells, Decorative & Hard Coatings.

MP2 series consists of mainly two units. The first unit is the DC power supply, which provides DC power into the big capacitor bank of the pulse unit. The second unit is the Pulsar, an intelligent circuitry, which is equipped with highly sophisticated ARC

VOLTAGE PULSING - Descrete Advantage

MAGPULS MP2 Pulse Generators are designed on Voltage Pulsing Technology (VPT). Unlike in Current Pulsing Technology, users can set the amplitude of the Pulse (voltage) in VPT Pulsars. This provides a very tight control on the process. Stable plasma condition is easily achievable at low pulsing frequencies, well below 100kHz. Pulsing current is in correlation with the plasma impedance & temperature stress on the coating products can be controlled very effectively.

Features and Benefits

Adjustable Pulse Parameters & Frequency	
6 Different Output operating modes	
DC, Uni-Polar Pulse, Bi-Polar Pulse & Programmable Puls Train	
Enhanced Effective ARC management	

Independent +ve and -ve Pulse & Arc Parameters Different adjustable voltage amplitude for positive and negative pulse



- management capability. MP2 series units are available with an output power range from 3 kW up to 60 kW and pulse current from 35 A up to 400 A peak current.
- MP2 Duty Cycle can be adjusted individually for each half wave to achieve higher target utilisation & for better optimisation of the processes. Enhanced ARC management provides best coating results without process interruptions. Optionally, MP2 series provides an external Optical Input Interface for external controlling of the pulse times externally. It also has as an Optical Output Interface for triggering or synchronization of other bipolar pulse power supplies of series MP1 or MP2.

>	Universal Application Range One power supply
>	Optimal adjustment of process for better process stability
	Better control of power optimized target utilization
	Quick Arc-suppression. Lowest Arc-energy. Best results
>	Highly Effective results for Dual Sputtering processes

	MP2-35 AS	MP2-100 AS	MP2-200 AS	MP2-400 AS
OUT PUT				
Voltage	0 - 1000 V			
Current	0 - 5.3 A DC 0 - 35 A Pulse	0 - 38 A DC 0 - 100 A Pulse	0 - 50 A DC 0 - 200 A Pulse	0 - 120 A DC 0 - 400 A Pulse
Power	2x 0 - 3 kW DC	2x 0 - 15 kW DC	2x 0 - 30 kW DC	2x 0 - 60 kW DC
Pulse Frequency	DC or 0.05 Hz - 50 kHz			
Max. Frequency with Max. Pulse Current	100 kHZ at 10 A 25 kHZ at 35 A	100 kHZ at 25 A 20 kHZ at 100 A	100 kHZ at 50 A 20 kHZ at 200 A	100 kHZ at 80 A 20 kHZ at 400 A
Pulse Time Settings Ton+ / Ton- / Toff+ / Toff-	2.0 µs up to 100 sec			
Duty Cycle	0.005 % to 100 %			
Pulse wave form	DC+, DC- Unipolar+ pulse, Unipolar- pulse Programmable Pulse Train			
IN PUT				
Max. Voltage	2x 0 - 1000 V DC			
Max. Current	2x 0 - 5.3 A DC	2x 0 - 38 A DC	2x 0 - 50 A DC	2x 0 - 120 A DC
Max. Power	2x 0 - 3 kW DC	2x 0 - 15 kW DC	2x 0 - 30 kW DC	2x 0 - 60 kW DC
Mains Supply	1 Φ 230 V AC 50/60 Hz or 1 Φ 115 V AC 50/60 Hz			
ARC-MANAGEMENT	0 to ±35 A peak	0 to ±100 A peak	0 to ±200 A peak	0 to ±400 A peak
ARC-Detection Time			• • • • • • • • • • • • • • • • • • • •	
Off Time after ARC-	< 200 ns			
Detection	30 µs up to 1000 ms			
ARC-Recovery Time	≥ 100 µs			
di/dt Dynamic Change	Var. di/dt threshold: 0 A/µs up to 2000 A/µs			
Voltage Drop ΔU	Var. U threshold: 0 % up to 100 % Ubc (Option)			
U x I - Cross Detection	Var. U threshold: 0 V up to 1000 V Var. I threshold: 0.1 x max. Ipeak up to 1 x max Ipeak (Option)			
INTERFACE				
Analog	1 (up to 3) 15 pin-Sub-D for controlling external DC power supplies			
Digital	15 pin Sub-D user Interface with floating potential contactors			
RS 232	9 pin Sub-D			
Ethernet		RJ	45	
Profibus	9 pin Sub-D (Option)			
TEMP MANAGEMENT				
Cooling System	Air cooling Water cooling (max. water pressure 6 bar)			
Cooling Temperatur	Max. 35°C 20°C - 30°C			

MP2-35 AS	MP2-*
	1
	19"-Rad
222.25 mm x 48	
25 kg	32
	F
Graphical menu	ı via functio
Har	d Coating o
PVD, PI	asma Nitric Dual & S
	222.2 25 kg Graphical menu Hare

Please contact us for information on higher capacity models & other variants

BP Symmetric & BP Asymmetric

MP2 Pulse Generators are available in 2 variants : Bi-Polar Symmetric (MP2-S) & Bi-Polar Asymmetric (MP2-AS). In Symmetric variant, +ve and -ve Pulses will have the same Pulse Voltage settings, whereas in Asymmetric variant, users can set different values for Pulse Voltage outputs. This gives the user higher control and advantage in the Dual Magnetron Sputteirng processes.

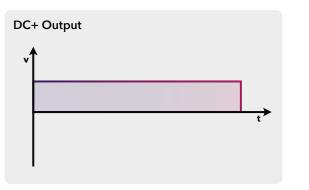
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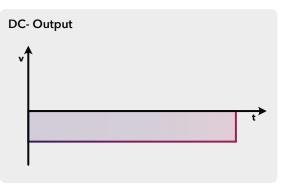


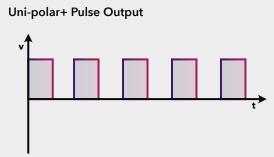
100 AS MP2-200 AS		MP2-400 AS	
+ 5 °C up t	to + 35 °C		
80 % non c	ondensing		
1500 m abo	ve sea level		
ack 5 HU		19"-Rack 6 HU	
83 mm x 65() mm	266.7 mm x 483 mm x 650 mm	
2 kg	36 kg	65 kg	
Graphic co	lor display		
Power, OK,	Start / Stop		
ion keys, arro	ow keys and continou	us rotating knob	
on Tools & I	Bits and BIAS applica	tion	
-	Plasma, Reactive Spu netron Sputtering	ttering,	
Met	als		

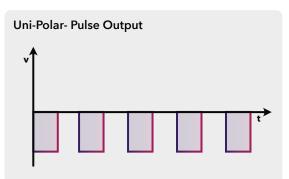


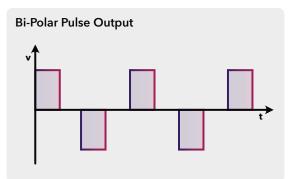
OUT PUT Waveforms











Programmable Pulse Train Output				
v†	пп			
			t	